## **AMENDMENTS TO THE CLAIMS**

- 1. (currently amended) A photoresist composition, comprising an admixture of a phenolic resin and an onium carboxylate salt, the dissolution rate of said photoresist composition in aqueous base is less than about  $1.3 \times 10^{-4} \, \mu \text{m/sec}$ .
- 2. (original) The photoresist composition of claim 1, wherein the onium carboxylate is an onium cholate, onium lithocholate, or onium deoxycholate.
- 3. (original) The photoresist composition of claim 2, wherein the onium cholate is an iodonium cholate.
- 4. (original) The photoresist composition of claim 3, wherein the iodonium cholate is an alkyloxyphenylphenyl iodonium cholate.
- 5. (currently amended) The photoresist composition of claim 4, wherein the alkyloxyphenylphenyl iodonium cholate is octyloxyphenylphenyl octyloxyphenylphenyl iodonium cholate.
- 6. (original) The photoresist composition of claim 1, wherein the phenolic resin is novolac.
- 7. (original) The photoresist composition of claim 1, wherein the onium carboxylate is present in an amount of at least 20 wt%.
- 8. (original) The photoresist composition of claim 1, wherein said photoresist composition can withstand pre-exposure baking temperatures of at least 125 °C.
- 9. (canceled)
- 10. (currently amended) A single component photoresist composition, comprising an onium cation protected carboxylate polymer.
- 11. (original) The photoresist composition of claim 10, wherein the polymer is an acrylic/acrylic acid copolymer.
- 12. (original) The photoresist composition of claim 11, wherein the copolymer is a

methacrylic/acrylic acid copolymer.

- 13. (original) The photoresist composition of claim 10, wherein the onium cation is an iodonium cation.
- 14. (original) The photoresist composition of claim 13, wherein the iodonium cation is an alkyloxyphenylphenyl iodonium cation.
- 15. (currently amended) The photoresist composition of claim 14, wherein the alkyloxyphenylphenyl cation is an octyloxyphenylphenyl octyloxyphenylphenyl iodonium cation.
- 16. (original) The photoresist composition of claim 10, wherein the onium cation is present at a concentration of at least 25 mole%.